

Substitute Form 1449A/PTO

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(use as many sheets as necessary)

Sheet 1 of 1

Complete if Known

Application Number	10/091,373
Filing Date	March 4, 2002
First Named Inventor	Hiroshi ITO
Art Unit	1752
Examiner Name	Unassigned <i>M. W. JCC</i>
Attorney Docket Number	ARC920010125US1

U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No.	Document No.	Issue Date or Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date if Appropriate
<i>PCW</i>	AN	2002/0102490	8/1/02	Ito et al.			
	AO	Serial No. 09/771,149		Ito et al.			1/26/01
	AP	Serial No. 09/771,261		Brock et al.			1/26/01
<i>PCW</i>	AQ	Serial No. 09/794,466		Allen et al.			2/26/01

OTHER DOCUMENTS — NONPATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), Title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T
<i>PCW</i>	AR	Abe et al. (1995), "Study of ArF Resist Material in Terms of Transparency and Dry Etch Resistance," <i>Journal of Photopolymer Science and Technology</i> 8(4):637-642.	
	AS	Allen et al. (1995), "Resolution and Etch Resistance of a Family of 193 nm Positive Resists," <i>Journal of Photopolymer Science and Technology</i> 8(4):623-636.	
	AT	Endert et al. (1999), "Microstructuring with 157 nm Laser Light," <i>Proceedings of SPIE-The International Society for Optical Engineering</i> 3618:413-417.	
<i>PCW</i>	AU	Onishi et al. (1991), "Acid Catalyzed Resist for KrF Excimer Laser Lithography," <i>Journal of Photopolymer Science and Technology</i> 4(3):337-340.	

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OCT 29 2002

TC 1700

Examiner Signature	<i>Sam C. Wada</i>	Date Considered	3/4/2004
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Substitute for form 1449A/PTO

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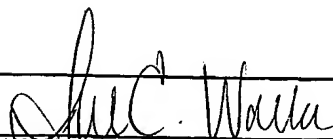
U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No.	Document No.	Issue Date or Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date if Appropriate
JCW	AA	5,344,742	9/6/94	Sinta et al.			
JCW	AB	6,087,064	7/11/00	Lin et al.			

OTHER DOCUMENTS — NONPATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), Title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T
JCW	AC	Chiba et al. (2000), "157 nm Resist Materials: A Progress Report," <i>Journal of Photopolymer Science and Technology</i> 13(4):657-664.	
	AD	Choi et al. (2000), "Design and Synthesis of New Photoresist Materials for ArF Lithography," <i>Advances in Resist Technology and Processing XVII, Proceedings of SPIE</i> 3999:54-61.	
	AE	Ito et al. (1981), "Methyl α -Trifluoromethylacrylate, an E-Beam and UV Resist," <i>IBM Technical Disclosure Bulletin</i> 24(2):991.	
	AF	Ito et al. (1982), "Polymerization of Methyl α -(Trifluoromethyl)acrylate and α -(Trifluoromethyl)Acrylonitrile and Copolymerization of These Monomers with Methyl Methacrylate," <i>Macromolecules</i> 15(3):915-920.	
	AG	Ito (1984), "Radical Reactivity and Q-e Values of Methyl α -(Trifluoromethyl)acrylate," <i>Macromolecules</i> 17(10):2204-2205.	
	AH	Ito et al. (1987), "Anionic Polymerization of α -(Trifluoromethyl)acrylate," <i>Recent Advances in Anionic Polymerization, Elsevier</i> , pp. 421-430.	
	AI	Ito et al. (2001), "Novel Fluoropolymers for Use in 157 nm Lithography," <i>Journal of Photopolymer Science and Technology</i> 14(4):583-593.	
	AJ	Ito et al. (2001), "Polymer Design for 157 nm Chemically Amplified Resists," <i>Advances in Resist Technology and Processing XVIII, Proceedings of SPIE</i> 4345:273-284.	
	AK	Kunz et al. (1999), "Outlook for 157 nm Resist Design," <i>Proceedings of SPIE</i> 3678:13-23.	
	AL	Schmidt et al. (1962), "Ozonisierung Cyclischer Enolather," <i>Liebigs Ann. Chem. Bd.</i> 656:97-102.	
JCW	AM	Willson et al. (1983), "Poly(Methyl α -Trifluoromethylacrylate) as a Positive Electron Beam Resist," <i>Polymer Engineering and Science</i> 23(18):1000-1003.	

Examiner Signature



Date

Considered

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